PMMA / P(MMA-MAA) BILAYER PROCESS

 Spin P(MMA-MAA) copolymer 13% solution in ethyl lactate. You should refer to this as "copolymer," not as "EL13," since "EL" is an abbreviation for the solvent ethyl lactate. Spin for about 2 minutes or until the film looks uniform. Bake at 180°C for about 2 minutes. The bake time and temperature are not critical.

Approximate thickness of P(MMA-MAA) EL13 spun at 3krpm: 800 nm Confirm this with a profilometer after scratching the film with tweezers. The thickness of this bottom layer is critical for tunnel-junction processes that use angled evaporation (eg the Dolan process or the bridge-free process.)

- 2. Let the wafer cool at least 30 seconds after removing it from the hotplate.
- Spin 950k MW PMMA, 3% or 4% solution in anisole.
 Spin for about 1 minute or until the film looks uniform.
 Bake at 180°C on a hotplate, for about 2 minutes. The bake time and temperature are not critical.

Approximate thickness of 3% PMMA spun at 3 krpm: 150 nm Approximate thickness of 4% PMMA spun at 3 krpm: 200 nm

Confirm the total thickness by scratching the film with tweezers and using a stylus profilometer (the Dektak or Alphastep)

- 4. Expose at 100 kV Typical large-area dose is 1000 μ C/cm² Be sure to include the standard dose test AND the standard undercut test on each substrate.
- 5. Develop in IPA:water 3:1 at 5°C for 2 minutes. The longer development time is necessary because the resist layer is thick, about 1 μ m. You can use other temperatures, but it is important to be consistent. The development temperature is important.

For a larger undercut, use 10:1 IPA:water at 5°C for 2 minutes (or choose some other temperature, but be consistent.)

Blow dry with nitrogen, or spin dry. Do not rinse in anything else, especially not alcohol.

 Liftoff: evaporate metal, eg 5 nm Cr then 20 nm Au, then soak off the PMMA in NMP at 150°C. Do not heat the NMP above 200°C. Alternatively, use acetone. Do NOT heat acetone, since it is highly flammable. Ultrasonic agitation will not really help, but go ahead if you are desperate.